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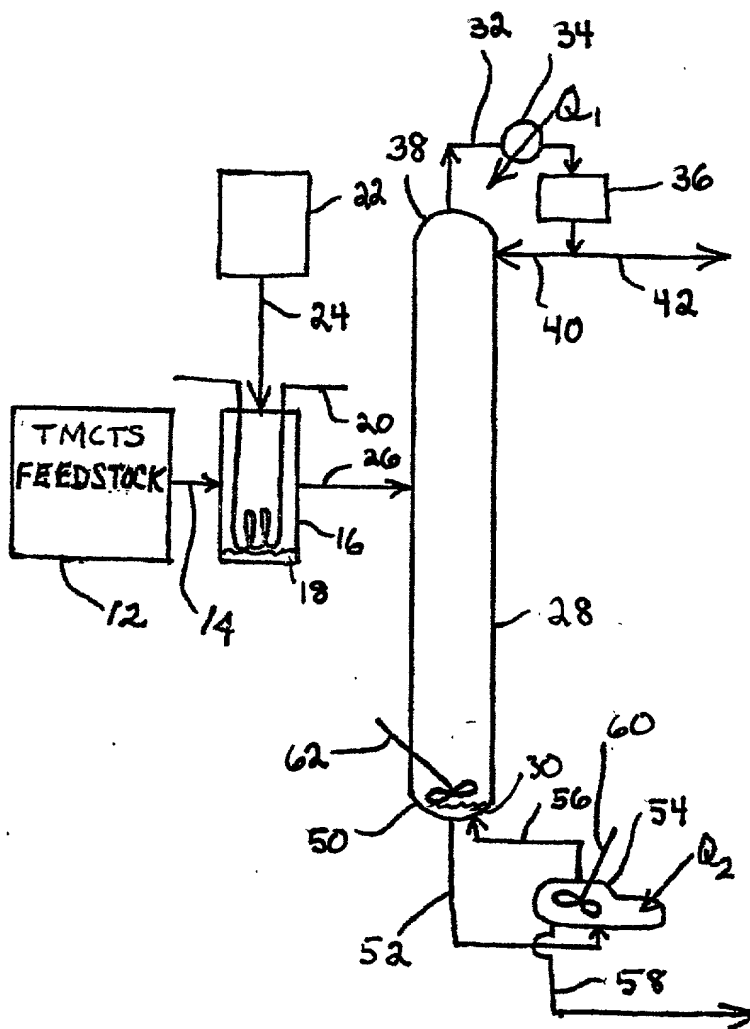


Figure 2 is a schematic diagram of a chemical vapor deposition (CVD) system. The system includes a precursor source (102) and a carrier gas source (116). The precursor source (102) is connected to a reactor (108) via a line (104). The carrier gas source (116) is connected to the reactor (108) via a line (118). The reactor (108) contains a substrate (106) and a heating element (110). The heating element (110) is connected to a power source (112) via a line (114). The reactor (108) is shown in cross-section, indicating the location of the substrate (106) and the heating element (110). The system is labeled 100.

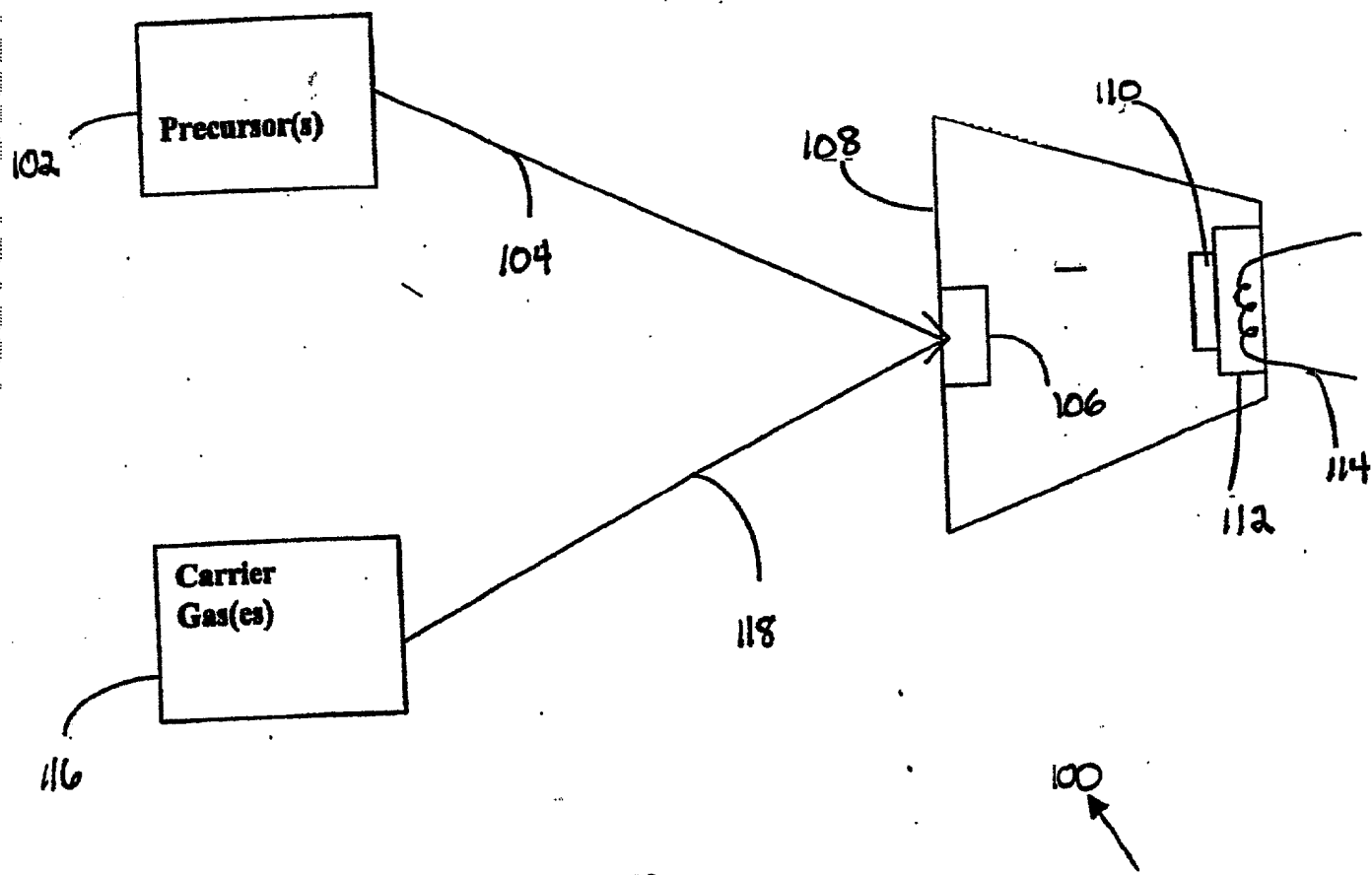


Figure 2